	Application No.	Applicant(s)	
	10/720,325	HSU, PING	
Notice of Allowability	Examiner	Art Unit	
	Asok K. Sarkar	2891	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in or other appropriate commits GHTS. This application is	n this application. If not included unication will be mailed in due course. T	
1. X This communication is responsive to amendment filed 12/0	<u>6/2005</u> .		
2. The allowed claim(s) is/are <u>1-22</u> .			
 3. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents 	been received. been received in Applicati	on No	the
International Bureau (PCT Rule 17.2(a)).		5	
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file ENT of this application.	e a reply complying with the requirement	ts
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			F
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftspers	on's Patent Drawing Revie	w (PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			
6. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT			
	• •		*
Attachment(s)			
1. Notice of References Cited (PTO-892)	5. Notice of I	nformal Patent Application (PTO-152)	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)		lummary (PTO-413), /Mail Date	
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0	98), 7. ☐ Examiner's	Amendment/Comment	
Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit	8. ⊠ Examiner's	Statement of Reasons for Allowance	
of Biological Material	9. 🗌 Other	_·	
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DETAILED ACTION

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Response to Amendment

1. Applicant's explanation of the instant invention in pointing the difference with the cited prior art was found to be persuasive.

Allowable Subject Matter

- 2. Claims 1 22 are now allowed.
- 3. The following is an examiner's statement of reasons for allowance:

Claims 1 – 14 recite, inter alia, a method of fabricating a trench device structure comprising the steps of forming a second conductive layer overlying the first conductive layer in the deep trench, herein the second conductive layer is lower than the surface of the semiconductor substrate and a portion of the second conductive layer is isolated from the semiconductor substrate by the second portion of the collar insulating layer. The art of record does not disclose or anticipate the above limitation in combination with other claim elements nor would it be obvious to modify the art of record so as to form a device including the above limitation.

Claims 15 – 22 recite, inter alia, a method of fabricating a trench device structure with a single – side buried strap, comprising the steps of performing a tilt ion implantation on undoped polysilicon or amorphous silicon layer, wherein a portion of the undoped polysilicon or amorphous silicon layer in the deep trench is not implanted, selectively wet etching the undoped polysilicon or amorphous silicon layer, thereby exposing the underlying lining layer, sequentially etching the exposed lining layer and the contiguous collar insulating layer expose a portion of the semiconductor substrate

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using the doped polysilicon or amorphous silicon layer as a mask, and removal of the remaining lining layer and the doped polysilicon or amorphous silicon layer. The art of record does not disclose or anticipate the above limitation in combination with other claim elements nor would it be obvious to modify the art of record so as to form a device including the above limitation.

Conclusion

- 4. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."
- 5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Asok K. Sarkar whose telephone number is 571 272 1970. The examiner can normally be reached on Monday Friday (8 AM- 5 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, William B. Baumeister can be reached on 571 272 1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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6. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Asok K. Sarkar
December 19, 2005

Primary Examiner